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Nanotechnology and Microelectronics: Materials, Processing, Measurement, and Phenomena

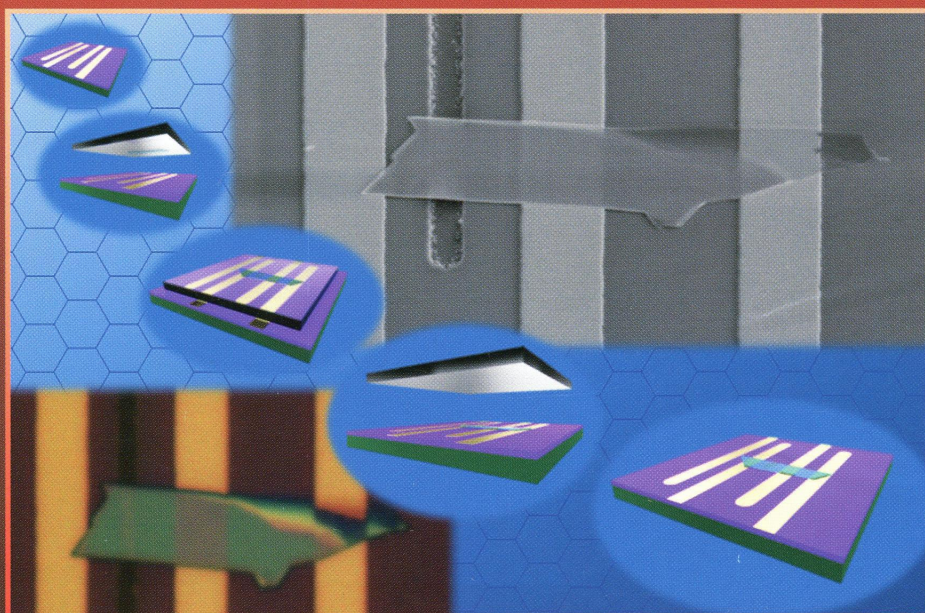


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Review Article:

**Oxide-based Chromogenic Coatings and Devices for Energy Efficient Fenestration:
Brief Survey and Update on Thermochromics and Electrochromics**

-by Claes G. Granqvist

Papers from the 58th International Conference on
Electron, Ion and Photon Beam Technology and Nanofabrication



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Nanotechnology and Microelectronics:

Materials, Processing, Measurement, and Phenomena

Second Series
Volume 32, Number 6
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Review Article

Oxide-based chromogenic coatings and devices for energy efficient fenestration: Brief survey and update on thermochromics and electrochromics

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On The Cover: Rui Yang, Xuqian Zheng, Zenghui Wang, Christopher J. Miller, and Philip X.-L. Feng, *JVST B* **32**(6), p. 061203-1. Cover shows a facile dry-transfer process for making 2D crystalline transistors and suspended structures. (lower left & upper right) Optical microscope and scanning electron microscope images of a flake of 2D crystal on electrodes and a narrow trench. (insets from upper left to lower right) Snapshot illustration of the dry-transfer process.